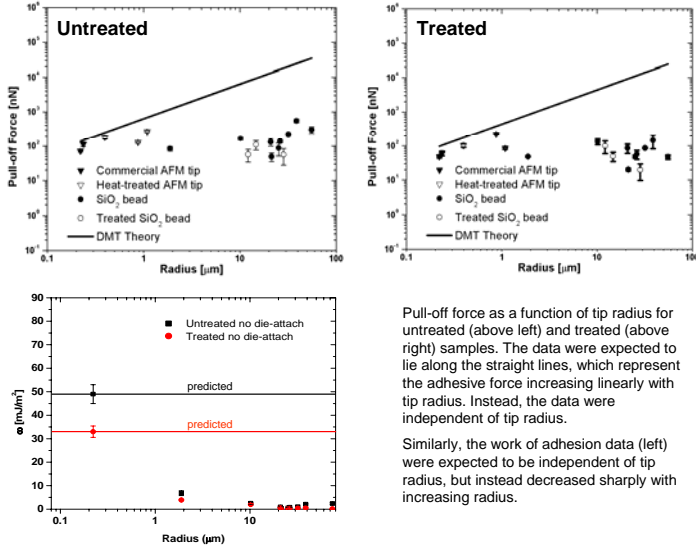


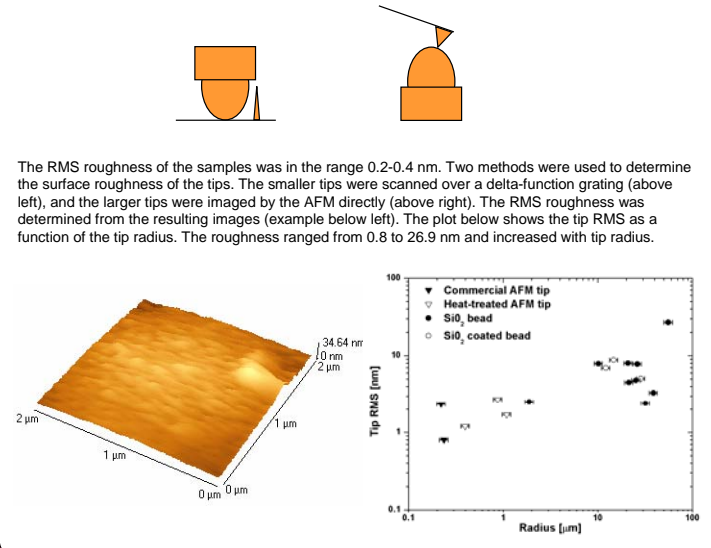
## Abstract

The adhesive (pull-off) force was measured between differently sized AFM (Atomic-Force Microscope) tips of different roughness and smooth sample surfaces that had well-controlled material properties. The samples were untreated and treated unpatterned silicon die and the tip sizes ranged from 200 nm to 60 μm, a range that brackets typical feature sizes in MEMS. We observed that the uncorrected pull-off force was independent of the radius of the AFM tip, which was contrary to all continuum-mechanics model predictions. We calculated a simple correction due to the measured RMS (Root Mean Square) surface roughness of the AFM tips, which resulted in the expected dependence of the pull-off force on radius, but with higher than expected magnitudes. The presence of a few small asperities can greatly reduce the adhesive force.

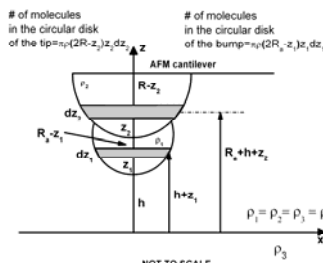
## Hypothesis and initial results



## Is the unexpected behavior due to roughness?



## A simple single-asperity model



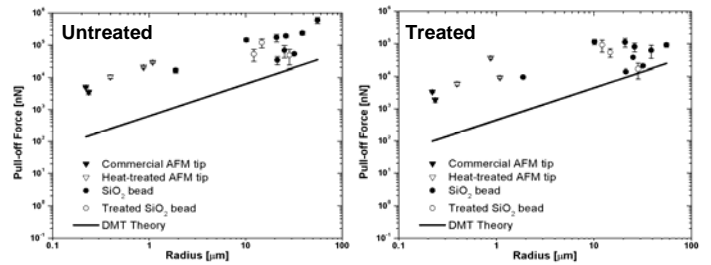
(1) Prediction:

$$F_{corrected}(R, R_a) = \frac{|F_{pull-off}|}{\left[ \frac{(h_c + 2R_a)h_c^3}{R(h_c + R_a)^3} - \frac{h_c}{R} + \frac{R_a}{R} + \frac{h_c^2}{(h_c + R_a)^2} \right] \left\{ \left[ 1 - \frac{3R}{2L} \tan \phi \right] \cos \phi \right\}}$$

(2) Keeping the largest terms:

$$F_{corrected}(R, R_a) = \frac{|F_{pull-off}| \sec \phi}{\left[ \frac{R_a}{R} + \left( \frac{h_c}{h_c + R_a} \right)^2 \right]}$$

## Corrected results and conclusions



Corrected pull-off force (Eq.1) as a function of tip radius for the untreated (left) and treated (right) silicon oxide samples. The correction for the RMS surface roughness resulted in the expected dependence of the pull-off force on radius, but the magnitudes were higher than expected. Details of this work are given in [1] and [2]. Delrio et al. [3] found a similar sensitivity to small "asperities" in their study of micromachined surfaces. At the atomic scale, Luan and Robbins [4] found that atoms themselves act as "asperities".

Equation 2 on the left shows that physically there is a competition between the attraction of the asperities to the substrate and their role in separating the tip and sample. When the roughness is low, the asperities act to keep the tip and sample just slightly away from smooth, strong contact. When the roughness is large, the asperity-sample attraction dominates. The two contributions are equal when, e.g. if  $R = 10 \mu\text{m}$ ,  $R_a = 6.5 \text{ nm}$  ( $h_c = 0.165 \text{ nm}$ ).

The presence of a few small bumps on the tip can greatly reduce the measured adhesion. A model with a single representative asperity recovers the expected dependence of the force on the tip radius.

## Materials and methods

- Adhesive (pull-off) force measured as the average value of the minimum in the retraction of 256 AFM force curves
- Seventeen tips of four different types ranging in radii from 200 nm to 60 μm, a size range corresponding to typical MEMS contacts
- Samples were unpatterned silicon die, some treated with a few angstroms of diphenylsiloxane
- Cantilever stiffness and tip radii determined by methods described in [5] and [6]
- Geometric corrections due to angle of repose described in [7]
- Integration of expected force follows derivations given in [8]

## References

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